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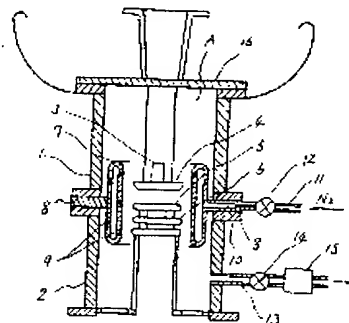
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 (22)Date of filing : **05.02.1986** (72)Inventor : **SHIRATORI RYUJI**

## (54) ION SOURCE FOR ION IMPLANTATION APPARATUS

### (57)Abstract:

**PURPOSE:** To safely remove contaminants or clinging substances from the electrodes of an ion source, by providing a gas ejector and an exhaust duct in the body of the ion source so that the clinging substances removed from the electrodes as lenses are sucked and collected by the dust.

**CONSTITUTION:** When an ion source is to be cleaned, it is put in a stopped state. After a valve for a vacuum pump for a vacuum container A which is the body of the ion source is closed, a shower valve 12 and an exhaust valve 14 are opened and a cleaning gas source and a suction unit 15 are put in action. Since the valve 12 is opened, a cleaning compressed gas is supplied into a hollow annular member 7 which is a gas ejector. The cleaning compressed gas is ejected from gas ejection holes 9 so that substances clinging to the surfaces of electrodes 4W6 and capable of being easily removed therefrom are blown away. The blown-away substances are sucked into the suction unit 15 by vacuum action and collected by a filter in the suction unit so that only the cleaning gas is released out of the vacuum container A. The electrodes 4W6 are thus cleaned.



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